### Chapter 10 The sp-block elements (III)

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### Group 13 Elements

- Electropositive character of elements still very important
- Atomic configurations ns<sup>2</sup> np<sup>1</sup>
- Bonding in the elements is much stronger and p orbital participation in bonding is important. sp<sup>2</sup> and sp<sup>3</sup> hybridization is common in compounds, except for In and especially Tl in oxidation state I ("inert pair" effect).

	melting pts. °C	boiling pts. °C	Density (g•cm <sup>3</sup> )	Form, properties
В	2030	3700	2.47	Brown, semicond.
Al	660	2350	2.70	Silvery metal
Ga	30	2070	5.91	Silvery, soft metal
In	157	2050	7.29	Silvery, soft metal
T1	304	1460	11.87	soft metal

### A highly variable group . . .

### Sources/uses of Group 13 elements

- Boron from  $Na_2B_4O_7 \bullet nH_2O$  (*borax*)
- ◆ Al from electrolysis.
- Ga is is a byproduct of Al production; In is a byproduct of Pb/Zn production; Tl must be separated from other "flue-dust" elements (Ni; Zn, Cd, In; Ge, Pb; As; Se, Te).
- Ga and In have uses in specialized semicond. devices (LEDs, junction metals, dopants in Si & Ge, photoconductors) and low-T solders.



### Some general group trends

- Boron has chemistry that more covalent, with some similarities to silicon in compounds with halogens and oxygen. The chemistry of boron-rich compounds is unique.
- Al, Ga, and In chemistry is dominated by oxidation state III. Bonds with "ligands" have polar covalent character.
- Tl has a prominent ox. state I chemistry.









# Diborane and other boron hydrides

- $B_2H_6$  (m.p. -165°C; b.p. -93°C) <u>Industrial Prep</u>:
  - $\begin{array}{l} 2 \; BF_3 + 6 \; NaH(s) \rightarrow B_2H_6(g) + 6NaF(s) \\ B_2H_6 \; \& \; many \; other \; boranes \; are \; spontaneously \\ flammable \; in \; air: \; B_2H_6 + 3 \; O_2 \rightarrow B_2O_3(s) + \\ 3H_2O \; \; \Delta H^\circ = -2165 \; kJ/mol \end{array}$
- Hydroboration w/ B<sub>2</sub>H<sub>6</sub> extremely important in organic chemistry (H.C Brown, Nobel, 1979).







## Boron-rich solids



Boron takes on many forms in the solid-state. The icosahedron is the basic building-block of all the forms and of many other boron-rich solids. This shows a cut-away of clusters from 4 layers of the simplest boron form! The network structure makes makes boron very hard and resistant to chemical attack.







### Boron chemistry - general comments

- Boron chemistry more like silicon than A1, ... eg.,
  - B(OH)<sub>3</sub> (*boric acid*) not at all basic. Al(OH)<sub>3</sub> amphoteric, but mostly basic.
  - B<sub>2</sub>O<sub>3</sub> and SiO<sub>2</sub> more similar in their network structures - both "acidic" (react with "basic" metallic oxides to form silicates and borates).
  - $BX_3$  and  $SiX_4$  (X = Cl, Br, I) all readily hydrolyzed. AlX<sub>3</sub> only partially hydrolyzed.
- Unique boron features: delocalized bonding in boron hydrides and remarkably diverse solid-state elemental and boron-rich chemistry.

#### Sources, uses of Boron

- ◆ B(OH)<sub>3</sub>;
- ♦ Na<sub>2</sub>B<sub>4</sub>O<sub>7</sub>•10H<sub>2</sub>O (borax); Na<sub>2</sub>[B<sub>4</sub>O<sub>5</sub>(OH)<sub>4</sub>]•2H<sub>2</sub>O (kernite) - huge deposits in Boron, CA
- Detergents, soaps, enamels, herbicides, refractory borides. Boron is used to strenthen plastics, it is much stiffer and lighter than Al. Borates used in borosilicate glass (e.g., Pyrex)
   these are lower melting and much more workable than pure SiO<sub>2</sub>.

### Preparation of Boron

- <u>Reduction by metals</u>: e.g., by Mg (from electrolysis of MgCl<sub>2</sub>)
  - contamination by refractory metal borides a problem
- ◆ <u>Electrolytic reduction</u> of borates or tetrafluoroborates
   e.g, KBF<sub>4</sub> in KCl/KF (800°C) cheap, but purity only ~ 95%
- ◆ <u>Reduction of volatile boron compounds</u> by H<sub>2</sub> - 2 BBr<sub>3</sub> + 3H<sub>2</sub> → 6HBr + B > 99% (Ta filament ~ 1000°C)
- - $-\ 2\ BI_3 \rightarrow \alpha \text{-rhombohedral }B + 3I_2 \qquad > 99\% \text{ (hot Ta filament)}$

#### **Boron Trihalides**

- Halides of p-block elements are key intermediates - boron no exception
- <u>Prep</u>: direct reaction for X = Cl, Br, I;
- ◆ BF<sub>3</sub>:

 $B_2O_3 + 3CaF_2 + 6H_2SO_4 \rightarrow$ 

 $2BF_3(g) + 3 "H_3O+[HSO_4-]" + 3CaSO_4(s)$ 

- strong B-F bond, insoluble  $CaF_2$ , acid-base rxn
- ◆ BX<sub>3</sub> all good Lewis acids:
  - acidity:  $BF_3 < BCl_3 < BBr_3$

#### **Boron Trihalides**

- Halides exchange is facile (why so easy?), e.g,:
  BF<sub>3</sub> + BCl<sub>3</sub> = BF<sub>2</sub>Cl + BCl<sub>2</sub>F, typical K ~ 0.5 2
- BF<sub>3</sub> is most versatile reagent in presence of H<sub>2</sub>O because others completely hydrolyzed:

 $\begin{array}{ll} BX_3+H_2O\rightarrow B(OH)_3+HX & hydrolysis \, (X=Cl,\,Br,\,I) \\ BX_3+ROH\rightarrow B(OR)_3+HX & alcoholysis \, (X=Cl,\,Br,\,I) \\ BF_3+xs\,H_2O\rightarrow 3H_3O^++3\,BF_4^-+B(OH)_3 & (heat) \\ BF_4^-: very \ stable \ anion \end{array}$ 

• BF<sub>3</sub> especially useful in Friedel-Crafts-like acylations and alkylations.

## Oxo compounds of Boron

Boric acid,

$$\begin{split} B(OH)_3 + H_2O &\to B(OH)_3(H_2O) = [B(OH)_4]^- + H_3O^+ \\ \text{at neutral pH, get condensation (similar to Al chem):} \\ 3 \ B(OH)_3 + H_2O = [(B_3O_3)(OH)_4]^- + H_3O^+ \quad K = 1.4 \times 10^{-7} \\ Na[(B_3O_3)(OH)_4] + 2NaOH (heat) \to \\ Na_3[(B_3O_3)O_3] \quad \text{Pyrex precursor} \end{split}$$

• Borate Esters in acid:  $B(OH)_3 + 3CH_3OH \rightarrow B(OCH_3)_3 + 3H_2O$ 

 $B(OCH_3)_3$  is a weaker Lewis acid than  $BF_3$  (why?)

### Boron-Nitrogen compounds

- Other compounds; amine-boranes:  $(^{1/}_2) B_2H_6 + NEt_3 \rightarrow H_3B_3:NEt_3 \text{ solid (adduct)}$
- ◆ B=N (alkene analogs) very reactive:
  "H<sub>2</sub>B=NH<sub>2</sub>" → B<sub>3</sub>N<sub>3</sub>H<sub>12</sub> "cyclohexane" analog
- ♦ <u>Borazine</u>: 1926 (Stock):  $\binom{1}{2}$  B<sub>2</sub>H<sub>6</sub> + NH<sub>3</sub> → B<sub>3</sub>N<sub>3</sub>H<sub>6</sub> <u>not</u> benzene-like, e.g., B<sub>3</sub>N<sub>3</sub>H<sub>6</sub> + 3 HCl → (NH<sub>2</sub>BHCl)<sub>3</sub>
- ◆ borazine derivatives prepared by alternate routes: reflux C<sub>6</sub>H<sub>5</sub>Cl: 3NH<sub>4</sub>Cl + 3BCl<sub>3</sub> → (NHBCl)<sub>3</sub> + 9 HCl(g) (NHBCl)<sub>3</sub> + 3NaBH<sub>4</sub> → (NHBH)<sub>3</sub> + (<sup>3</sup>/<sub>2</sub>)B<sub>2</sub>H<sub>6</sub>(g) + 3NaCl (NHBCl)<sub>3</sub> + 3RMgCl → (NHBR)<sub>3</sub> + MgCl<sub>2</sub>(s)

## Boron-Nitrogen compounds

• Boron Nitride:

 $\begin{array}{ll} 1200^{\circ}\text{C:} & \text{B}_2\text{O}_3+2 \ \text{NH}_3(\text{g}) \rightarrow 2 \ \text{BN}(\text{s})+3\text{H}_2\text{O}(\text{g}) \\ & 1800^{\circ}\text{C}, \ \text{high-P:} & \text{BN}(\text{s}, \ \text{hex}) \rightarrow \ \text{BN}(\text{s}, \ \text{cubic}) \end{array}$ 

# Hexagonal Boron Nitride



 Layers are graphitic, but stacking places N atoms in one layer above and below B atoms in adjacent layers (and vice versa).



adapted from Figure 12-13a, C&W

Reaction Summary: BCl<sub>3</sub>

